

VERSION WITH MARKINGS TO SHOW CHANGES MADE

13. For an imprint lithography process, a [The] system [of claim 12] capable of controlling the relative orientation and the relative gap between [calibrating and orienting] a template and [with respect to] a substrate surface to be imprinted comprising:

a pre-calibration stage for course movement and alignment of a template with respect to a substrate surface so that a gap is created between said template and said substrate surface; and

an orientation stage used in conjunction with said pre-calibration stage for fine movement and alignment of said template so that said gap is approximately uniform across that portion of said template that lies over said substrate surface.